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# INFORMATION DISCLOSURE STATEMENT BY APPLICANT

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Sheet	1	of	1
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**Complete if Known**

Application Number	09/422,398
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<b>Filing Date</b>	October 21, 1999
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First Named Inventor	Bruce W. Smith
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Group Art Unit	<del>Unknown</del>
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Examiner Name	Unknown
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Attorney Docket Number	88405.99R077
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## U.S. PATENT DOCUMENTS

[illegible]

**FOREIGN PATENT DOCUMENTS**

[illegible]

**Examiner  
Signature**

Nguyen, Hung Henry

Date \_\_\_\_\_

**Considered**

12/26/00

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**INFORMATION DISCLOSURE  
STATEMENT BY APPLICANT**

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Sheet 2 of 2

**Complete If Known**

Application Number	09/422,398
Filing Date	October 21, 1999
First Named Inventor	Bruce W. Smith
Group Art Unit	Unknown 2851
Examiner Name	Unknown
Attorney Docket Number	88405.99R077

**OTHER PRIOR ART -- NON PATENT LITERATURE DOCUMENTS**

Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.

Examiner Initials	No.	Other Prior Art	T <sup>2</sup>
HN	15	S. Asai, et al., "High Performance Optical Lithography Using a Separated Light Source", <u>J. Vac. Sci. Technology</u> , Vol B 10(6), pp. 3023-3026, (November/December 1992).	
HN	16	E. Tamechika, et al., "Investigation of Single Sideband Optical Lithography Using Oblique Incidence Illumination", <u>J. Vac. Sci. Technology</u> , Vol. B 10(6), pp. 3027-3031, (November/December 1992).	
HN	17	W.N. Partlow, et al., "Depth of Focus and Resolution Enhancement for i-line and Deep-UV Lithography Using Annular Illumination", <u>SPIE Optical/Laser Microlithography</u> , Vol. 1927, pp. 137-156, (1993).	
HN	18	T. Ogawa, et al., "The Effective Light Source Optimization With the Modified Beam For the Depth-of-Focus Enhancements", <u>SPIE Optical Laser Microlithography</u> , Vol. 2197, pp. 19-30, (1994).	
HN	19	T. Ogawa, et al., "Sub-Quarter Micron Optical Lithography With Practical Super Resolution Technique", <u>SPIE Optical Laser Microlithography VIII</u> , Vol. 2440, pp. 772-783, (1995).	
HN	20	B. W. Smith, et al., "Illumination Pupil Filtering Using Modified Quadrupole Apertures", <u>SPIE Optical Microlithography XI</u> , Vol. 3334, pp. 37-47, (1998).	
HN	21	B.W. Smith, et al., "Influences of Off-Axis Illumination on Optical Lens Aberration", <u>J. Vac. Sci. Technology</u> , Vol. B16(6) 3398, pp. 3405-3410, (November/December 1998).	
HN	22	Chin C. Hsia, et al., "Customized Off-Axis Illumination Aperture Filtering for Sub 0.18 um KrF Lithography", <u>SPIE Optical Microlithography XI</u> , Vol. 3679, pp. 39-46, (1999).	
HN	23	P. Zandbergen, et al., "Optical Extension at the 193nm Wavelength", <u>SPIE Optical Microlithography XI</u> , Vol. 3679, pp. 29-38, (1999).	
HN	24	Z. Yang, et al., "Corrections of Aberrations Using HOE's in UV and Visible Imaging Systems", <u>SPIE International Lens Design Conference</u> , Vol. 1354, pp. 323-327, (1990).	
HN	25	B. W. Smith, <u>Microlithography: Science and Technology</u> , Chapter 3, New York: Marcel Dekker (1998), pp. 216-231.	

Examiner Signature

Neygen, Hung Henry

Date

Considered

12/26/00

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